

Title (en)

POST TREATMENT OF A COATED SUBSTRATE WITH A GAS CONTAINING EXCITED HALOGEN TO REMOVE RESIDUES

Title (de)

NACHBEHANDLUNG EINES BESCHICHTETEN SUBSTRATES MIT EINEM ANGEREGTES HALOGEN ENTHALTENDEN GAS FÜR DIE BESEITIGUNG VON RÜCKSTÄNDEN

Title (fr)

POST-TRAITEMENT D'UN SUBSTRAT PORTANT UN REVETEMENT, AVEC UN GAZ CONTENANT UN HALOGENE ACTIVE POUR ENLEVER DES RESIDUS

Publication

**EP 0710161 A1 19960508 (EN)**

Application

**EP 94922123 A 19940712**

Priority

- US 9407751 W 19940712
- US 9241793 A 19930716

Abstract (en)

[origin: WO9502472A1] Material that has previously been subjected to a removal treatment is removed from a substrate by being contacted with a gas containing an excited halogen at a pressure of greater than 50 torr.

IPC 1-7

**B08B 3/12**; B08B 5/00; B08B 6/00; B08B 7/00; B08B 7/02; B08B 7/04; C03C 23/00; C23G 1/00; G03C 5/00

IPC 8 full level

**G03F 7/36** (2006.01); **B08B 3/02** (2006.01); **B08B 5/00** (2006.01); **B08B 6/00** (2006.01); **C03C 17/32** (2006.01); **C03C 23/00** (2006.01); **C23F 1/00** (2006.01); **C23F 1/12** (2006.01); **C23F 4/00** (2006.01); **C23G 5/00** (2006.01); **G03F 7/42** (2006.01); **H01L 21/302** (2006.01); **H01L 21/306** (2006.01); **H01L 21/311** (2006.01); **H05K 3/26** (2006.01)

CPC (source: EP)

**C03C 17/32** (2013.01); **C03C 23/00** (2013.01); **G03F 7/42** (2013.01); **H01L 21/02046** (2013.01); **H01L 21/31138** (2013.01); **C03C 2218/328** (2013.01)

Designated contracting state (EPC)

DE

DOCDB simple family (publication)

**WO 9502472 A1 19950126**; DE 710161 T1 19970130; EP 0710161 A1 19960508; EP 0710161 A4 19970416; JP H09502646 A 19970318

DOCDB simple family (application)

**US 9407751 W 19940712**; DE 94922123 T 19940712; EP 94922123 A 19940712; JP 50465295 A 19940712